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(54) Title: **PHOTOSENSITIVE RESIN COMPOSITION**

(57) Abstract: The present invention relates to a photosensitive resin composition capable of being developed by an alkaline aqueous solution, and provides a photosensitive resin which has superior resolving power by having a chemical bond between a binder resin and a crosslinking compound as well as a chemical bond between binder resin chains at an exposed area during an exposure process, thus maximizing a solubility difference between an exposed area and a non-exposed area during a developing process, and which has process benefits as well as superior film characteristics by reducing a consumed amount of a crosslinking compound, thus minimizing total amount of UV irradiation necessary.

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